Holonyak et al. Respond: Rather than a divergence between the results obtained on quantum-well heterostructures (QWH) grown by metal-organic chemical-vapor deposition (MO-CVD) and molecular-beam epitaxy (MBE), there may actually be some convergence. In the Comment above, Miller and co-workers mention that island growth in MBE QWH's is sensitive to temperature, and becomes worse if the substrate temperature deviates ± 50 °C from some unspecified temperature T_s . Apparently most of the work, with no observed clustering, that these workers cite involves the use of MBE QWH crystals grown at \leq 600 °C. The best *MBE* QWH laser crystal of which we are aware, however (i.e., the only one to have operated continuously at 300 K), has been grown at > 600 $^{\circ}$ C (~ 650 $^{\circ}$ C) and, moreover, operates (at high excitation level, $>10^3$ A/cm²) as a laser 30-40 meV (~ $\hbar\omega_{\rm LO}$) below the n=1 electron-to-light-hole or the electron-to-heavy-hole transitions (8518 and 8567 Å; see Fig. 2 of Tsang et al., Ref. 1; confined-particle transitions unmarked). This behavior agrees with the type of results we have reported for MO-CVD QWH lasers grown at $750 \, {}^{\circ}C$,^{2,3} and can be explained by clustering.4

All of the work on QWH's [MBE, MO-CVD or LPE (liquid-phase epitaxy)] is sufficiently new, and totally sensitive and dependent upon the crystal-growth process and choice of experimental parameters, so that it is not established yet in any great detail what T_s and other experimental conditions are optimum for each growth processs. Probably all of these crystal-growth processes will be subject to clustering for certain substrate temperatures, growth rates, and choice of crystal compositions (x in Al_xGa_{1-x}As). For example, more of a problem with clustering, at certain temperatures, might exist near the direct-indirect transition ($x \equiv x_c \sim 0.45$ for Al_xGa_{1-x}As). As we have shown,⁴ however, one solution to the problem of clustering in Al_xGa_{1-x}As is simply to substitute AlAs coupling and isolation barriers in Al_xGa_{1-x}As-GaAs QWH's. This permits also certain freedom in choice and manner of QWH crystal growth.

N. Holonyak, Jr., and W. D. Laidig Electrical Engineering Research Laboratory and Materials Research Laboratory University of Illinois at Urbana-Champaign Urbana, Illinois 61801

K. Hess

Electrical Engineering Research Laboratory and Coordinated Science Laboratory University of Illinois at Urbana-Champaign Urbana, Illinois 61801

J. J. Coleman and P. D. Dapkus

Rockwell International, Electronics Research Center Anaheim, California 92803

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